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- Method of forming silicon dioxide glass films.
- The manufacture of semiconductor devices and, specifically, deposition of SiO₂ coatings on semiconductor devices by oxidation decomposition of siloxanes is disclosed.

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EUROPEAN SEARCH REPORT

EP 88 10 5561

				levant	CLASSIFICATION OF THE
gory		ant passages	to	claim	APPLICATION (Int. CI.5)
Υ	EP-A-0 212 691 (FOCUS S INC.) * column 7, line 45 - column		MS 1-4	,9,10	H 01 L 21/205 C 23 C 16/46 H 01 L 21/316 C 23 C 16/40
	-	- -	6-8		0 23 0 10/40
A D,Y	US-A-4 168 330 (G. KAGAI * column 2, line 15 - column	NOWICZ) 3, line 6; claims 1,2,6 *		,9,10	
D,A		•	6-8	'	
A	US-A-3 834 939 (K.D. BEYER et al.) * column 2, lines 26-54; column 3, lines 1-52; claim 1 *		1-1	1	
Α	CHEMICAL ABSTRACTS vo stract no. 168679y, Columbia al.: "Thermal and radiation-in ane layers produced by an e & Khim. Vys. Energ. 1977, v	us, Ohio, US; V.A. SUTYAG nduced degradation of poly electron-beam method"	GIN et /silox-		
					TECHNICAL FIELDS
					SEARCHED (Int. CI.5)
					H 01 L C 23 C
	The present search report has I	peen drawn up for all claims			
- · - · -	Place of search Date of completion of search				Examiner
	Berlin	15 October 90			KLOPFENSTEIN P R
CATEGORY OF CITED DOCUMENTS X: particularly relevant if taken alone Y: particularly relevant if combined with another document of the same catagory A: technological background			E: earlier patent document, but published on, or after the filing date D: document cited in the application L: document cited for other reasons		
O:	non-written disclosure intermediate document theory or principle underlying the in	nvention	&: member of document		e patent family, corresponding